

<b>Notice of References Cited</b>	Application/Control No. 10/725,139		Applicant(s)/Patent Under Reexamination SATO ET AL.	
	Examiner Elias Desta		Art Unit 2857	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-2005/0011611	01-2005	Mahoney et al.	156/345.24
*	C	US-2005/0199341	09-2005	Delp et al.	156/345.24
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	K	US-			
	L	US-			
	M	US-			

#### FOREIGN PATENT DOCUMENTS

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#### NON-PATENT DOCUMENTS

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	V	Coumou, 'Advanced RF Metrology for Plasma Process Control', October 2003, MKS Instruments, pages 1-5
	W	Khargonekar et al., 'Intelligent Electronics Manufacturing: Modeling and Control of Plasma Processing', August 1998, UOM Publication, pages 1-57
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.